



Connected machines made real - Reniver showcase

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Are you getting the most out of your machines? Do you want to know how to get more out of your machines? Access to hidden machine data, events and control options may be helpful. By making your machines connected in a simple, cyber-secure and (re)usable way, you have everything at hand to improve productivity and quality. In order to meet this challenge, Reniver developed the Reniway application with the support of VLAIO.

During the Reniver showcase event at our Open House Advanced Manufacturing on September 13, Reniver will be showcasing its innovations and demonstrating how Reniway works with production machines and robots in Sirris' 4.0 Made Real Pilot Factory.

Connected production environment

At this [event](#) for machine builders, integrators and manufacturing companies, we will explain how Reniver can make your machines connected. The solution relies heavily on open standards such as OPC UA and MQTT **to make machines and robots universally available**. In the process, the data interface is standardised to make sure each machine is speaking the same universal 'production language'. This approach makes automation easier and ensures that dashboards, maintenance applications, cloud and AI applications use the relevant data without (much) integration work.

Showcases will demonstrate the power of standardisation on the machine in a tangible way. Since the Reniway application speaks the same 'production language' as the machines, it instantly recognises a new machine and automatically auto-configures the app operator screens, KPI calculations, alarm notifications and data sets for tracing/analysis.

The [event](#) will take place on Tuesday, September 13, from 11:00 to 12:00. Afterwards you are also welcome to attend Sirris' Open House where many new technological developments in advanced manufacturing will be demonstrated. More information on this Open House can be found [here](#).

Both events are free to attend, but registration is required.



(Source picture : [123RF](#))

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